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**Surface chemical analysis — Chemical methods for the collection of elements from the surface of silicon-wafer working reference materials and their determination by total-reflection X-ray fluorescence (TXRF) spectroscopy —**

**AMENDMENT 1**

*Analyse chimique des surfaces — Méthodes chimiques pour collecter les éléments analysés de tranches de silicium comme matériaux de référence pour l'analyse par spectroscopie de fluorescence X en réflexion totale (TXRF) —*

*AMENDEMENT 1*



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Amendment 1 to ISO 17331:2004 was prepared by Technical Committee ISO/TC 201, *Surface chemical analysis*.